INFORMATION DISCLOSURE STATEMENT BY APPLICANT

(Multiple sheets used when necessary) SHEET 1 OF 2

	PTO/SB/08 Equivalent
Application No.	10/540,056
Filing Date	June 22, 2005
First Named Inventor	Sato et al.
Art Unit	1795
Examiner	John S Y Chu
Attorney Docket No.	SHIGA7.021APC

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U.S. PATENT DOCUMENTS					
Examiner Initials Cite No. Cite No. Document Number Number - Kind Code (if known) Example: 1,234,567 B1		Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	
	1	7,312,014	12-25-2007	Maesawa et al.	
	2	US 2004/0033438	02-19-2004	Hamada et al.	
	3	6,949,329	09-27-2005	Endo et al.	
	4	6,630,282	10-07-2003	Oomori et al.	
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	6	US 2003/232273	12-18-2003	Adams et al.	
	7	US 2006/247346	11-02-2006	Hojo et al.	

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Examiner Initials	Cite No.	Foreign Patent Document Country Code-Number-Kind Code Example: JP 1234567 A1	Publication Date MM-DD-YYYY	Name of Patentee or Applicant	Pages, Columns, Lines Where Relevant Passages or Relevant Figures Appear	T ¹
	8	JP 2003-107707	04-09-2003	Clariant (Japan) KK		√ abstract
	9	JP 2003-075998	03-12-2003	Matsushita Elec. Inc. Co., Ltd.		√ abstract
	10	JP 2004-078153	03-11-2004	Sumitomo Chem. Co., Ltd.		√
	11	JP 2002-062655	02-28-2002	Tokyo Ohka Kogyo Co., Ltd.		√ abstract
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	15	WO 03/007079	01-23-2003	Wako Pure Chem. Ind., Ltd.		
	16	JP H10-142799	05-29-1998	Toshiba Corp.	7-7-3-0111-0-1-3-01-2-3-3	√ abstract
	17	JP 2001-056558	02-27-2001	Tokyo Ohka Kogyo Co., Ltd.		1
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Examiner Initials	Cite No.		
	21	Office Action Issued on July 1, 2008, on the Japanese Patent Application No. 2004-142581.	

Examiner Signature

Date Considered

*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

		F 10/0b/00 Equivalent
	Application No.	10/540,056
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STATEMENT BY APPLICANT	First Named Inventor	Sato et al.
STATEMENT BY AFFLICANT	Art Unit	1795
(Multiple sheets used when necessary)	Examiner	John S Y Chu
SHEET 2 OF 2	Attorney Docket No.	SHIGA7.021APC

		NON PATENT LITERATURE DOCUMENTS	
item (book, magazine, journal, serial, symposium		Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T ¹
	22	NAKAMURA et al., "Ultra Thin Film Resist for Low Energy E-beam Projection Lithography", Journal of Photopolymer Science and Technology, Vol. 15, No. 3, pp. 417-422, (2002)	
		YOSHIZAWA et al., "Comparative study of resolution limiting factors in electron beam lithography using the edge roughness evaluation method", Journal of Vacuum Science and Technology B, Vol. 19, Issue 6, pp. 2488-2493, (2001)	
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